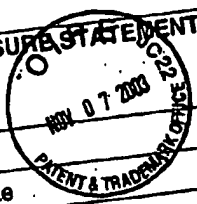


U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. AMAT/6392/DSM/LO W K/JW	Serial No. 10/010,950
SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant Xia, et al.	Confirmation No.: 5694
(Use several sheets if necessary)		Filing Date November 13, 2001	Group 2818
Examiner Dung Anh Le			



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*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date if Appropriate
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	A2	5,926,740	07/20/1999	Forbes, et al.	438	763	10/27/1997
	A3	5,876,891	03/02/1999	Takimoto, et al.	430	71	05/26/1995
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	A8	5,465,680	11/14/1995	Loboda	117	84	07/01/1993
	A9	5,242,530	09/07/1993	Batey, et al.	156	613	08/05/1991
	A10	5,224,441	07/06/1993	Felts, et al.	118	718	09/27/1991
	A11	5,011,706	04/30/1991	Tarhay, et al.	427	39	04/12/1989
	A12	4,759,947	07/26/1988	Ishihara, et al.	427	38	10/04/1985
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*Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
	B1	09-008031	JP	H01L	21/316	<input type="checkbox"/>	<input checked="" type="checkbox"/>
<i>de</i>	B2	00/19498	WO	H01L	21/027	<input type="checkbox"/>	<input checked="" type="checkbox"/>
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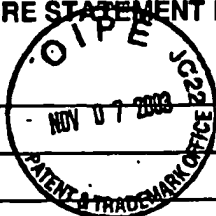
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*Examiner Initial	Including Author, Title, Date, Pertinent Pages, Etc.	
<i>de</i>	C1	U.S. Patent Application No. 09/270,039, filed on March 16, 1999.
	C2	Written Opinion from PCT/US99/22424, dated April 5, 2001.
	C3	PCT Partial International Search Report for US99/22317 dated March 21, 2000.
		Date Considered <i>Mar-2004</i>

Examiner

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not consid red. Include copy of this form with your communication to applicant.

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	A2	2003/0129827	07/10/2003	Lee, et al.	438	629	07/15/2002
	A3	2003/0111730	06/19/2003	Takeda, et al.	257	758	05/28/2001
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	A9						
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Dle	C4	PCT International Search Report for US99/22425 dated February 11, 2000.
	C5	Dijkstra, et al. "Optimization of Anti-Reflection Layers for Deep UV Lithography", Proceeding of SPIE Optica/Laser Microlithography, Bellingham, SPIE, Volume 1674, (1992) Pages 362-375.
	C6	Omar, M.A. "Elementary Solid State Physics: Principles and Applications," Lowell Technological Institute, Addison-Wesley Publishing Company, 1975, Pages 124 & 125.
	C7	Fukuda, et al. "Highly Reliable SiOF Film Formation by ECR-CVD using SiF ₂ H ₂ ", (1996) Symposium on VLSI Technology Digest of Technical Papers, IEEE, Pages 114-115.
	C8	PCT International Search Report for US/02/40034, dated May 19, 2003.
Dle	C9	Wu, et al, "Advanced Metal Barrier Fee Cu Damascene Interconnects with PECVD Silicon Carbide Barriers for 90/65-nm BEOL Technology", 2002 IEEE Pages 595-598.

Examiner Dle Date Considered Mar-2004

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<i>Dle</i>	A1	6,147,009	11/14/2000	Grill, et al.	438	780	06/29/1998
	A2	6,054,379	04/25/2000	Yau, et al.	438	623	02/11/1998
	A3						
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*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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<i>Dle</i>	B1	1 107 303	06/13/2001	EP	H01L	21/316	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B2	99/41423	08/29/1999	WO	C23C		<input type="checkbox"/>	<input checked="" type="checkbox"/>
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*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
<i>Dle</i>	C1	PCT International Search Report for US/02/36229 dated 09/03/2003 (AMAT/6392.PC)
	C2	
	C3	
Examiner	<i>Dle</i>	
Date Considered	Mar-2004	

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	A2	6,500,773	12/31/2002	Gaillard, et al.	438	790	11/27/2000
	A3	2003/0085408 A1	05/08/2003	Yang, et al.	257	77	11/02/2001
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	A13						

Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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<i>[Signature]</i>	B1	199 04 311 A1	08/12/1999	Germany	C23C	16/44	<input checked="" type="checkbox"/>	<input type="checkbox"/>
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	C1	
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	C3	

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